## Vanishing atomic migration barrier in SiO2

Nature 390, 596-599

DOI: 10.1038/37581

Citation Report

#	Article	IF	CITATIONS
1	Stability of Solid State Reaction Fronts. Physical Review Letters, 1998, 81, 2490-2493.	7.8	17
2	Effect of Particle Size on Rate of Coalescence of Silica Nanoparticles. Journal of Colloid and Interface Science, 1999, 213, 258-261.	9.4	31
3	Structuring thin films via ion beams. , 2000, , 407-421.		O
4	On Kinetically vs. Energetically Driven Growth Instabilities in Solid and Vapor Phase Epitaxy. Materials Research Society Symposia Proceedings, 2000, 618, 233.	0.1	O
5	Epitaxial recrystallization of alkali-ion implanted $\hat{l}$ ±-quartz. Nuclear Instruments & Methods in Physics Research B, 2000, 166-167, 148-153.	1.4	7
6	The use of high pressure in basic, materials, and life sciences. , 2000, 128, 3-27.		12
7	Morphological instability of growth fronts due to stress-induced mobility variations. Applied Physics Letters, 2000, 77, 516-518.	3.3	27
8	Molecular Dynamics Study of the Self-Diffusion of lons in B2O3Melt at High Pressure. Journal of Physical Chemistry A, 2001, 105, 7973-7978.	2.5	16
9	Pressure-enhanced molecular self-diffusion in microporous solids. Microporous and Mesoporous Materials, 2001, 42, 113-119.	4.4	48
10	Enhanced crystallization and phase transformation of amorphous silicon nitride under high pressure. Journal of Materials Research, 2001, 16, 67-75.	2.6	3
11	Epitaxial crystallization of keV-ion-bombarded α quartz. Journal of Applied Physics, 2001, 89, 3611-3618.	2.5	23
12	Chapter 15 Transport properties in deep depths and related condensed-matter phenomena. Developments in Geochemistry, 2004, 9, 1041-1203.	0.1	O
13	Current Conduction and Dielectric Behavior of High k-Y2O3 Films Integrated with Si Using Chemical Vapor Deposition as a Gate Dielectric for Metal-Oxide-Semiconductor Devices. Journal of Electroceramics, 2004, 13, 121-127.	2.0	12
14	Mechanism of oxide deformation during silicon thermal oxidation. Physica B: Condensed Matter, 2006, 376-377, 407-410.	2.7	10
15	Enhanced Si and B diffusion in semiconductor-grade SiO2 and the effect of strain on diffusion. Thin Solid Films, 2006, 508, 270-275.	1.8	6
16	Transport Mechanism of Interfacial Network Forming Atoms during Silicon Oxidation. Japanese Journal of Applied Physics, 2006, 45, 694-699.	1.5	15
17	Mechanical strength and coordination defects in compressed silica glass: Molecular dynamics simulations. Physical Review B, 2007, 75, .	3.2	91
18	TiO2nanoparticle trails in garnet: implications of inclusion pressure-induced microcracks and spontaneous metamorphic-reaction healing during exhumation. Journal of Metamorphic Geology, 2007, 25, 451-460.	3.4	11

## CITATION REPORT

#	Article	IF	CITATIONS
19	Atmospheric pressure induced atomic diffusion into solid crystal. Physical Review B, 2009, 79, .	3.2	10
20	Coesite and quartz characteristic of crystallization from shock-produced silica melt in the Xiuyan crater. Earth and Planetary Science Letters, 2010, 297, 306-314.	4.4	28
21	Enhanced one dimensional mobility of oxygen on strained LaCoO3(001) surface. Journal of Materials Chemistry, 2011, 21, 18983.	6.7	64
22	Brittle to Ductile Transition in Densified Silica Glass. Scientific Reports, 2014, 4, 5035.	3.3	119
23	Impact of pressure on the structure of glass and its material properties. MRS Bulletin, 2017, 42, 734-737.	3.5	16
24	Densification Mechanisms of Oxide Glasses and Melts. , 2018, , 343-369.		10
25	First-principles study of pressure and SiO-incorporation effect on dynamical properties of silicon oxide. Japanese Journal of Applied Physics, 2019, 58, 111004.	1.5	2